

ELECTRON BEAM ANALYZER

Patent Number: JP2002310959
Publication date: 2002-10-23
Inventor(s): MITAMURA SHIGEHIRO; HAYASHI KOJI
Applicant(s): SHIMADZU CORP
Requested Patent: JP2002310959
Application Number: JP20010117011 20010416
Priority Number(s):
IPC Classification: G01N23/225; G01N1/28; G01N1/32; G01N1/34; H01J37/20; H01J37/252; H01J37/28
EC Classification:
Equivalents:

Abstract

PROBLEM TO BE SOLVED: To achieve a three-dimensional analysis on bulk samples.

SOLUTION: Inside an analysis chamber 3, an electron beam irradiation part 4 is provided to generate electron beams B made to irradiate a sample S, an X-ray spectral detector 5 which spectrally detects X rays R generated from the sample, an electron detector 6 which detects electrons E generated from the sample and the like. A glow discharging part 8 is arranged near an analyzing position P1 where the sample is irradiated with the electron beams--as an etching position P2. A sample stage 7 is provided to move the sample S between the two positions. After the etching of the surface of the sample at the P2, analysis on the surface of the sample is repeated at the P1, thereby achieving a three-dimensional analysis for obtaining the three-dimensional information distribution of the sample.

Data supplied from the esp@cenet database - I2